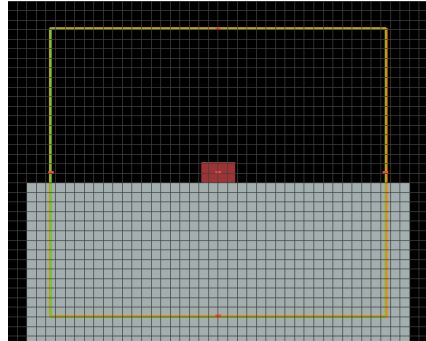


Project 2 (chip #2)

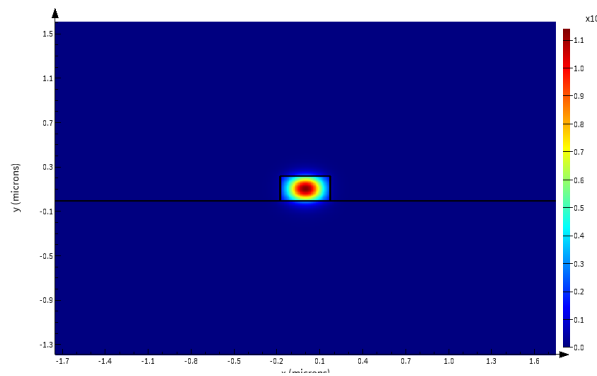
- Fabricated at UBC with the ZEP Process
- Main difference from Chip 1: Air Cladding and new input from on-chip laser

Design Process

- Start by understanding waveguide properties
 - Waveguide with 350 nm width is used so that compatibility is maintained with the components in the provided PDK.
 - Waveguide has dimensions 350x220 nm, has air cladding and sits on an SiO₂ layer
 - This should be fairly accurate since there is no significant process bias on this platform
 - Simulated in MODE with the following parameters:
 - 3.5x3.0 um simulation area
 - 400x400 mesh cells



- Simulated Group Index: 4.724525
- Energy density distribution:



- Interferometer
 - Lock in L1, L2, delta L for good interferometer function
 - Formula from simulated group index gives delta L = 2699 um
 - Beck-of-the-chocolate-wrapper estimate: $\Delta L = \frac{c}{\Delta v \cdot n_g}$ gives path length difference of 2.538181 mm
 - Have not simulated in INTERCONNECT since there is some concern about the accuracy of the waveguide models, see Piazza

Floorplan

- 605*410 um
- Two devices:
 - Main interferometer uses calculated path length difference and sends output to first and third grating couplers
 - Input can come from either on-chip laser or second grating coupler, routed into the two inputs of the first directional coupler
 - Second device is just a pair of grating couplers to allow calibrating insertion loss when using the external laser
- Several verification errors: overlapping DevRec regions near the directional couplers, and a disconnected pin where the waveguide enters the cell. Seems normal.
- Testability
 - Grating couplers and spacing
 - 127 um grating coupler spacing is required
 - Input on fibre 2
 - Named fibre 2 like opt_in_TE_1310_device_RonNelson_comment